

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Janusz Murakowski et al.

Confirmation No.: 1853

Application No.: 10/707,854

Filed: January 16, 2004

Art Unit: 2823

For: ETCHLESS FABRICATION OF PLANAR  
PHOTONIC CRYSTAL STRUCTURES IN  
HIGH REFRACTIVE INDEX MATERIAL

Examiner: F. L. Toledo

**AMENDMENT AFTER FINAL REJECTION**

MS AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

August 15, 2006

Dear Sir:



**INTRODUCTORY COMMENTS**

In response to the Final Office Action mailed August 8, 2006, the following Amendments and remarks are submitted to place the above-identified U.S. patent application in condition for allowance.

**Amendments to the Claims** begin on page 2 of this paper.

**Remarks/Arguments** begin on page 5 of this paper.

No fees are believed to be due with this Amendment after Final.